

Katsuyoshi Kodera

List of Publications by Year in descending order

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Version: 2024-02-01

18
papers

76
citations

1684188
5
h-index

1588992
8
g-index

18
all docs

18
docs citations

18
times ranked

33
citing authors

#	ARTICLE	IF	CITATIONS
1	A simulation study on bridge defects in lamellae-forming diblock copolymers. , 2018, , .		1
2	Fabrication of Sub-10 nm Metal Wire Circuits using Directed Self-Assembly of Block Copolymers. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2016, 29, 647-652.	0.3	1
3	Reactive ion etching challenges for half-pitch sub-10-nm line-and-space pattern fabrication using directed self-assembly lithography. Proceedings of SPIE, 2016, , .	0.8	0
4	Characterization of half-pitch 15-nm metal wire circuit fabricated by directed self-assembly of polystyrene-block-poly(methyl methacrylate). Microelectronic Engineering, 2016, 159, 21-26.	2.4	4
5	Control of morphological defects at the boundary between the periodic and non-periodic patterns in directed self-assembly process. Proceedings of SPIE, 2016, , .	0.8	1
6	Sub-10nm lines and spaces patterning using grapho-epitaxial directed self-assembly of lamellar block copolymers. Proceedings of SPIE, 2016, , .	0.8	0
7	Directed self-assembly lithography for half-pitch sub-15 nm pattern fabrication process. Materials Research Society Symposia Proceedings, 2015, 1750, 24.	0.1	4
8	A simulation study for defects in sub-15 nm line-space using directed self-assembly. Materials Research Society Symposia Proceedings, 2015, 1750, 36.	0.1	3
9	A Simulation Study on Defectivity in Directed Self-assembly Lithography. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2015, 28, 683-688.	0.3	5
10	A Challenge to the Micro-phase Separation Limit of PS-b-PMMA by Doping with Hydrophilic Materials. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2015, 28, 617-622.	0.3	0
11	Electrical yield verification of half-pitch 15nm patterns using directed self-assembly of polystyrene-block-poly(methyl methacrylate). Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2015, 33, .	1.2	5
12	Simulation study on defect annihilation dynamics in directed self-assembly lithography. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2015, 33, 06F303.	1.2	0
13	Directed self-assembly lithography using coordinated line epitaxy (COOL) process. Proceedings of SPIE, 2015, , .	0.8	7
14	A novel simple sub-15nm line-and-space patterning process flow using directed self-assembly technology. Microelectronic Engineering, 2015, 134, 27-32.	2.4	14
15	Defect-aware process margin for chemo-epitaxial directed self-assembly lithography using simulation method based on self-consistent field theory. Proceedings of SPIE, 2014, , .	0.8	4
16	Process Evaluation of Directed Self-assembly Lithography using Simulation Method based on Self-consistent Field Theory. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2014, 27, 31-36.	0.3	2
17	Dissipative particle dynamics simulations to optimize contact hole shrink process using graphoepitaxial directed self-assembly. Proceedings of SPIE, 2013, , .	0.8	10
18	Novel error mode analysis method for graphoepitaxial directed self-assembly lithography based on the dissipative particle dynamics method. , 2013, , .		15